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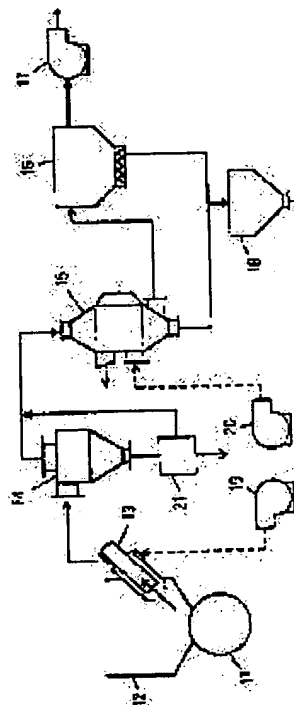
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KASAHARA MASARU**(54) DEVICE AND METHOD FOR REGULATING CHLORINE CONCENTRATION OF BYPASS DUST****(57)Abstract:**

PROBLEM TO BE SOLVED: To provide a bypass dust chlorine concentration regulating device and its method in which the chlorine concentration of the bypass dust to be recovered from the kiln exhaust gas can be regulated in a bypass device and a bypass method of the kiln exhaust gas.

SOLUTION: The dust contained in the exhaust gas extracted from a kiln 11 through a probe 13 is classified into a rough powder dust and a bypass dust, the rough powder dust is recovered from a lower end part of a cyclone 14 and introduced in a rough powder dust post-adding device 21, and the exhaust gas containing the bypass dust is discharged from the cyclone 14 and fed to a cooler 15. A part of the rough powder dust is added from the exhaust gas containing the bypass dust from the rough powder dust post-adding device 21, and the remaining part of the rough powder dust is returned to the kiln system again. Since a part of the rough powder dust low in chlorine concentration is mixed in the bypass dust high in chlorine concentration, the quantity of generation of the dust to be recovered by a dust collector 16 and the chlorine concentration can be regulated.

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